



SHEET 1 OF 1

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

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ATTY. DOCKET NO.
071971-0557SERIAL NO.
10/576,518APPLICANT
Tohru YAMAOKA, et al.FILING DATE
April 20, 2006GROUP
2614**U.S. PATENT DOCUMENTS**

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
/B.E./		US 4,142,073	02-27-1979	AGNEUS et al.	
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		JP 2002-209298	07-26-2002	SEIKO EPSON CORP		JAPAN (w/English Abstract)

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
/B.E./		United States Office Action issued in United States Patent Application No. US 10/591,456, mailed January 29, 2009.
/B.E./		European Search Report issued in European Patent Application No. EP 04818870.0, mailed March 12, 2009.
/B.E./		MAJAMAA, T., et al., "Effect of Oxidation Temperature on the Electrical Characteristics of Ultrathin Silicon Dioxide Layers Plasma Oxidized in Ultrahigh Vacuum", Physics Scripta, 1999, Pages 259-262, Vol. T79
/B.E./		ROSS, E.C., et al., "Effects of Silicon Nitride Growth Temperature on Charge Storage in the MNOS Structure", Applied Physics Letters, December 15, 1969, Pages 408-409, Volume 15 Number 12

EXAMINER
/Brian Ensey/DATE CONSIDERED
09/03/2009

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.